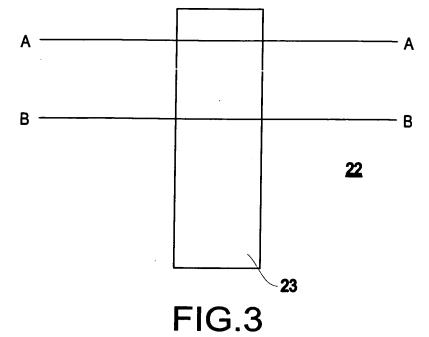


MASKING LAYER 1 23
SILICON 22
BURIED OXIDE 21
SUBSTRATE 20

FIG.2





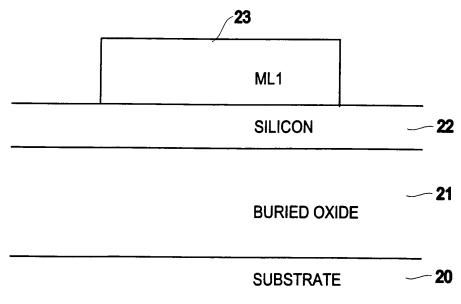
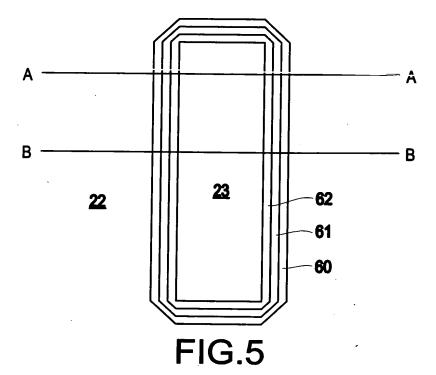
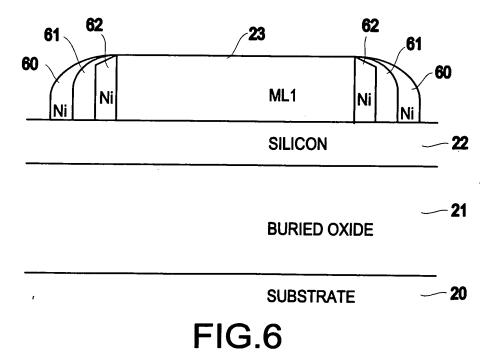


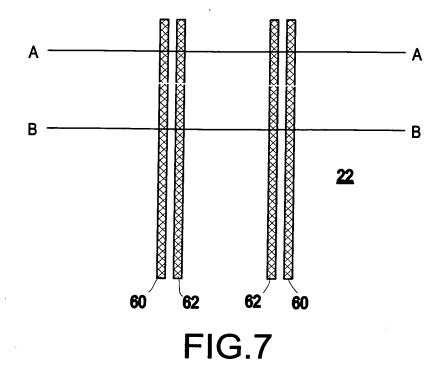
FIG.4











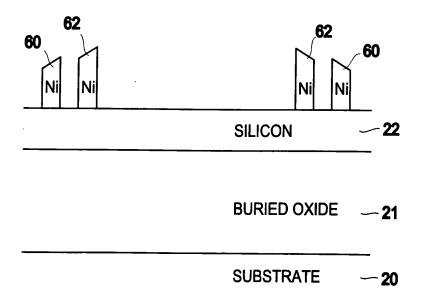


FIG.8



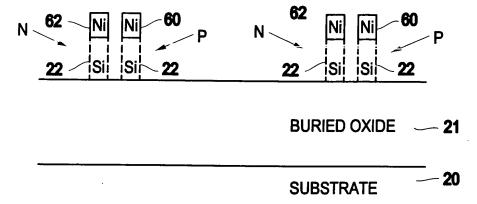


FIG.9

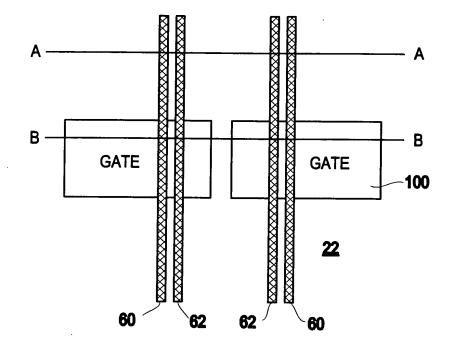
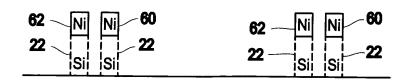


FIG.10





BURIED OXIDE ___ 21

SUBSTRATE -20

FIG.11

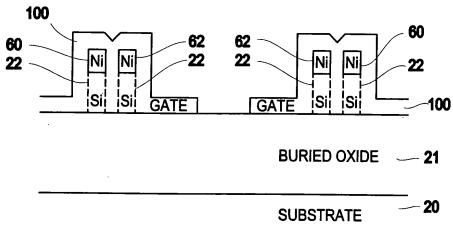
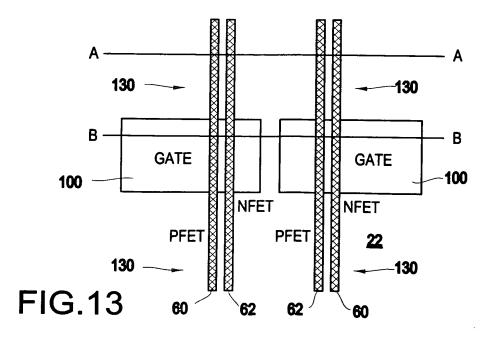
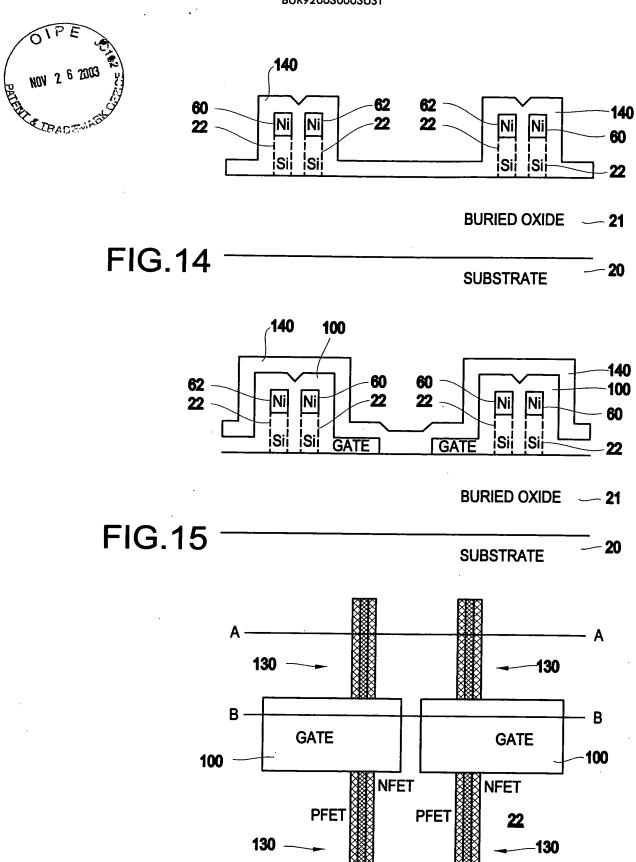


FIG.12





60

140

62

140

FIG.16

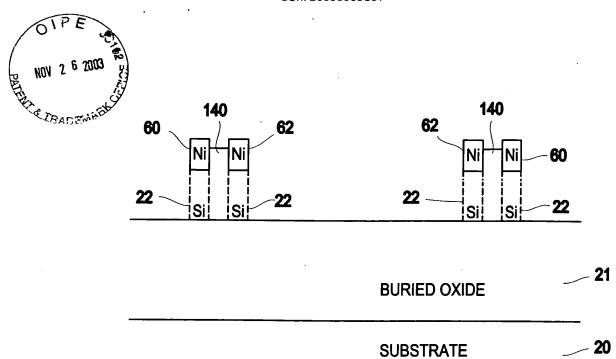


FIG.17

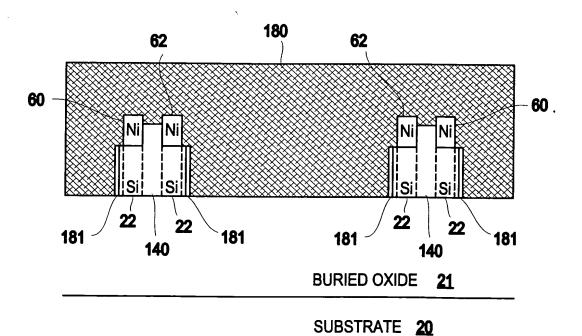


FIG.18

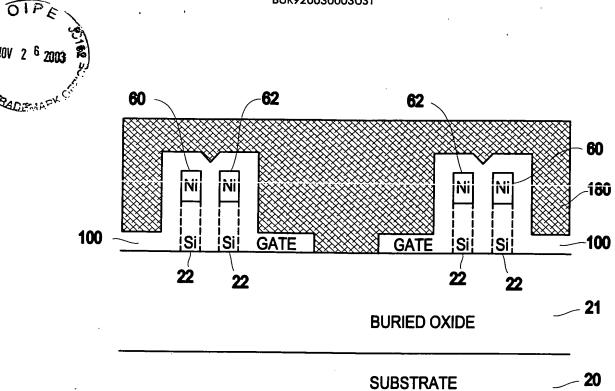


FIG.19

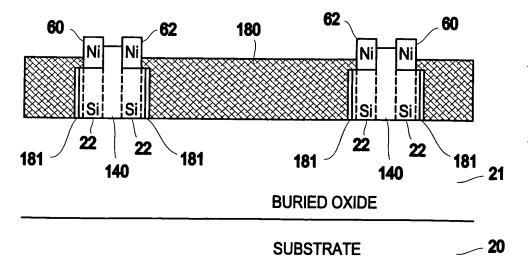


FIG.20



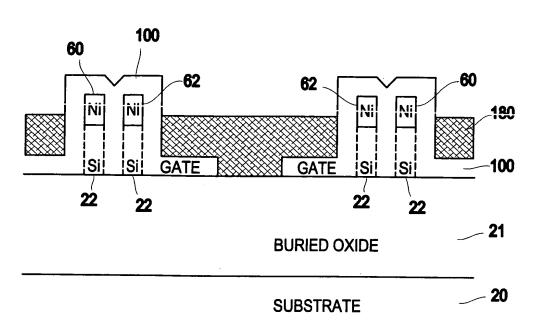


FIG.21

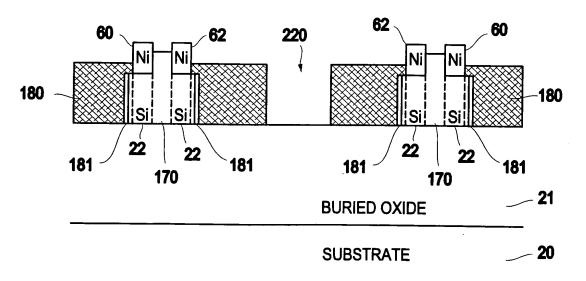


FIG.22

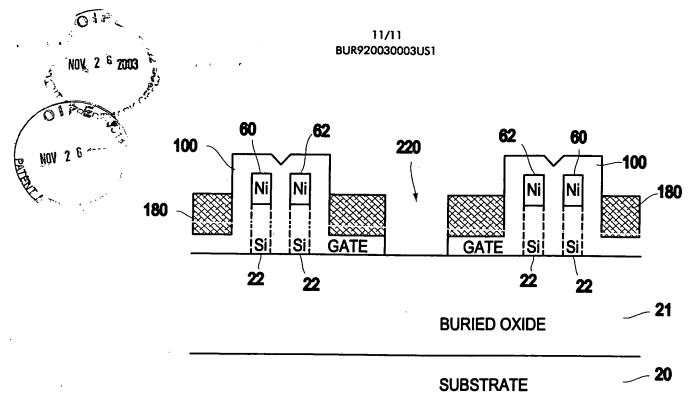


FIG.23

